

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	209207	(wafer or substrate) with (test\$6 or monitor\$6 or condition\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 17:25
L2	3716	1 same ((single adj crystal) or monocrystal\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 17:22
L3	1129	2 and ((tool or apparatus or chamber or system) with (test\$6 or check\$6 or monitor\$6 or calibrat\$6 or condition\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 17:24
L4	55	3 and ((wafer or substrate) with (reus\$6 or (re adj (usable or used))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 17:26
L5	51	4 and (@ad<"20031119" or @rlad<"20031119")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 17:27

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L11	741	wafer near5 (reus\$6 or (re adj (usable or used)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 16:08
L12	325	11 and test\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 16:08
L13	279	12 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 16:09
L14	223	13 and (tool or apparatus or chamber or system)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 16:10
L15	195	14 and (coat\$6 or deposit\$6 or replac\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 16:11
L16	187	15 and (@ad<"20031119" or @rlad<"20031119")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 16:11

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	9483	semiconductor near10 (tool or apparatus or system) near10 test\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 15:08
L4	33	2 and (wafer near10 (reus\$6 or (re adj used)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 15:11
L6	31	4 and (@ad<"20031119" or @rlad<"20031119")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 15:11

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L7	2008	semiconductor near10 (tool or apparatus or system) near10 test\$6 near10 wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 15:33
L8	445	7 and (wafer near10 (coat\$6 or deposit\$6 or recoat\$6 or crystal))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 15:34
L9	417	8 and (@ad<"20031119" or @rlad<"20031119")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/22 15:35